

Amendments to the Abstract

Please replace the Abstract on page 10 of the application with the following paragraph.

A method of fabricating a photomask includes transferring a ~~is disclosed.~~
~~The method facilitates accurate measurement of the photomask critical~~
~~dimension, without requiring the removal of the pellicle.~~ A first pattern is
~~transferred on~~ onto a substrate in a first area, and transferring at least one test
pattern is ~~transferred on~~ onto the substrate outside of the first area. A pellicle is
attached to the substrate, wherein ~~and~~ the pellicle covers the first area, but does
not cover the at least one test pattern.